

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-893001	Application No. 10/789,670
<b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)		Applicant Arun Ramamoorthy et al.	
		Filing Date February 27, 2004	Group Art Unit 1724
(37 CFR §1.98(b))			

**U.S. Patent Documents**

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

**Foreign Patent Documents or Published Foreign Patent Applications**

Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

**Other Documents (include Author, Title, Date, and Place of Publication)**

Examiner Initial	Desig. ID	Document
	AQ	Chauhan, M.M., et al., "Photoresist Outgassing in EUV", 2000 March Meeting: Bulletin of the American Physical Society, 45(1):563, abstract #L36.112, March 2000.
	AR	Moors, R., et al., "Electrostatic mask protection for extreme ultraviolet lithography", <i>Journal of Vacuum Science &amp; Technology B: Microelectronics and Nanometer Structures</i> , 20(1):316-320, Jan/Feb 2002.
	AS	
	AT	

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	